

Overview of silicon radiation detector technologies at FBK

Nicola Zorzi

Outline

- FBK organization and expertise
- Examples of radiation detector productions
- R&D on radiation detectors

“Fondazione Bruno Kessler” (<http://www.fbk.eu/>) is a research organization of the Autonomous Province of Trento



Areas of studies:

- Information Technology
- Materials and Microsystems
- Theoretical nuclear physics
- Public policy effectiveness
- Italian-German History
- Religious sciences

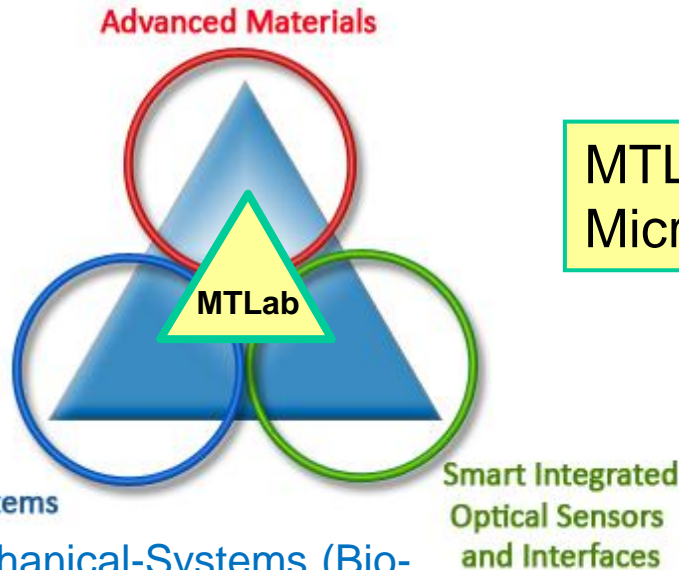
More than 350 researchers

CMM

Centre for Materials and Microsystems (<http://cmm.fbk.eu/>)

Organization: Research Units focused in three main areas

- New Materials and Analytical Methods for Biosensors and Bioelectronics (M2B2)
- MiNALab - Micro Nano Analytical Laboratory
- Biosint - Biofunctional Surfaces and Interfaces
- Plasma and Advanced Materials (PAM-SE)
- Interdisciplinary Laboratory for Computational Science (LISC)



MTLab
Micro Technology Laboratory

- BIO-Micro-Electro-Mechanical-Systems (Bio-MEMS)
- Micro-Electro-Mechanical-Systems (MEMS)
- Advanced Photonics and Photovoltaic (APP)
- **Silicon Radiation Sensors (SRS)**

- Smart Optical Sensors and Interfaces (SOI)
- 3D Optical Metrology (3DOM)

Micro Technology Laboratory

2 separate clean rooms:

- CR Detectors
500 m² in class 10 and 100
- CR MEMS
200 m² in Class 100 and 1000

Equipments:

- Lithography
- Diffusion
- Implantation
- Dry Etching
- Wet Etching
- Control Area



Test Laboratories

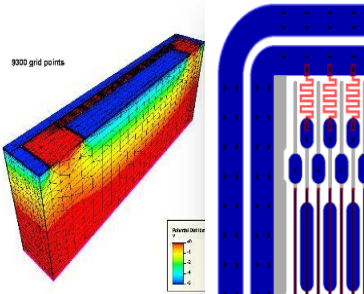
- Manual probers
- Automatic probers
- Parametric Test
- Functional Test (partial)

Now we are working with 4" wafers

An up-grade to 6" will take place
starting next month

Expertise

TCAD simulation
CAD design



Process flow
development

MTLab WebFabS v4.2

Job: MLM_aluminium

Run: MLM_aluminium Project: Internal
Technology: Technology Mask set: null
Device: testing Research unit: MTLab

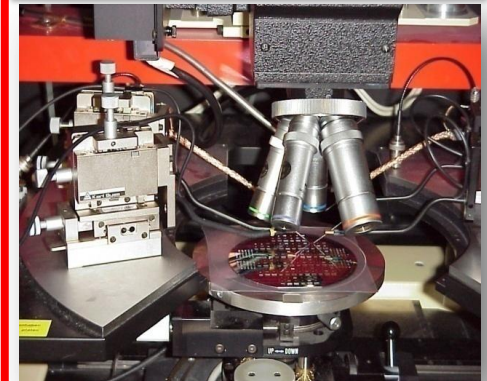
step	split	no	macro	description	status	note_in	note_out	l_wafer	wafer	step_in	step_out
1	1	1	Alu etch	etch	OK		Fatto da 9 a 14 da MLM_testing			2012-05-28 14:10:45	2012-05-28 15:02:13
2	1	1	SiPECRETE	deposited	OK					2012-05-28 15:02:13	2012-05-28 15:02:18
3	1	1	SiPECRETE	etch	OK					2012-05-28 15:02:18	2012-05-28 15:02:22
4	1	1	SiPECRETE	etch	OK					2012-05-28 15:02:22	2012-05-28 15:02:29
5	1	2	SiPECRETE	etch	OK	2 split		9-13-14		2012-05-29 08:25:34	2012-05-29 11:42:18
5	2	2	SiPECRETE	etch	OK	2 split		10-11-12		2012-05-29 11:42:18	2012-05-29 11:42:27
6	1	1	SiPECRETE	etch	OK					2012-05-29 11:42:27	2012-06-04 09:06:34
7	1	1	SiPECRETE	etch	OK					2012-06-04 09:06:34	2012-06-04 11:05:53
8	1	1	SiPECRETE	etch	OK					2012-06-04 11:05:53	2012-06-05 11:20:53
9	1	1	SiPECRETE	etch	OK					2012-06-05 11:20:53	2012-06-06 09:20:48



Fabrication



Device testing



People:

- **SRS**: 8 researchers

(3 design and simulation, 1 processing, 4 testing)

<http://srs.fbk.eu/en/home>



- **MTLab**: 3-4 researchers

(processing)

<http://mtlab.fbk.eu/>



Sensors for what kind

of radiation?

High-energy particles

- Ionizing particles
- X/ γ rays

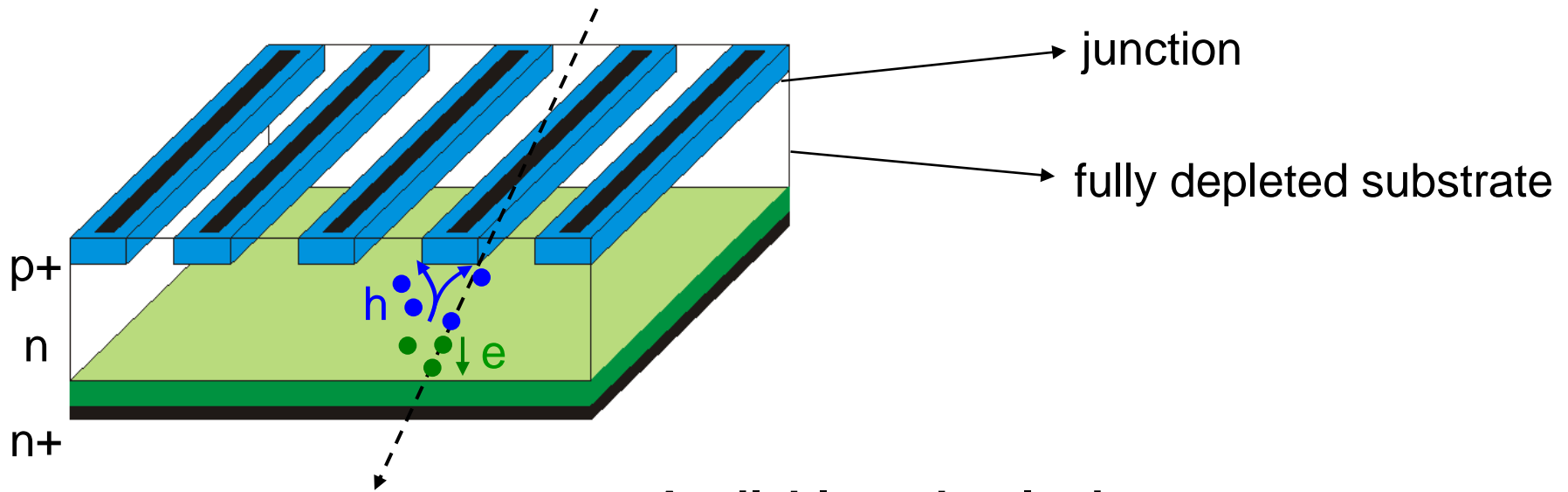
light

Mainly detection of extremely low intensity light

Main Applications

- Physics experiments
- Nuclear medicine
- Astrophysics
- Biology
- Material analysis

Radiation detectors



Types of detectors:

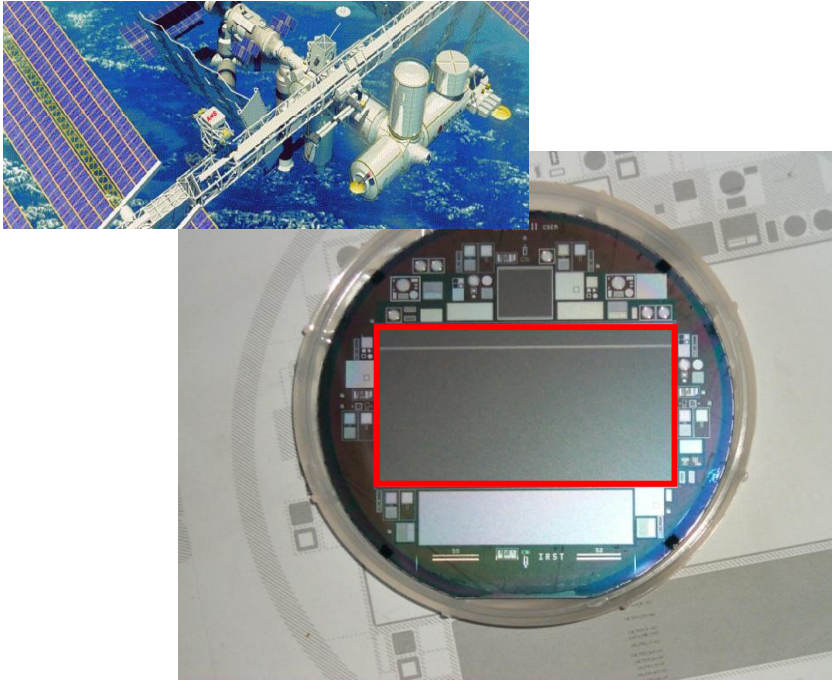
- Pixel detectors
- Strip detectors
- Drift detectors
- Pad detectors

Available technologies:

- n-in-p, n-in-n, p-in-n
- single- or double-side
- p-spray and p-stop isolation
- guard-ring termination
- gettering techniques
- punch-through and poly-resistor biasing
- integrated AC coupling capacitors

Strip Detectors: productions

AMS experiment (@ISS)



Silicon microstrip detectors:

700 large-area double-sided in spec detectors fabricated in 2002-2004.

ALICE experiment (@LHC)



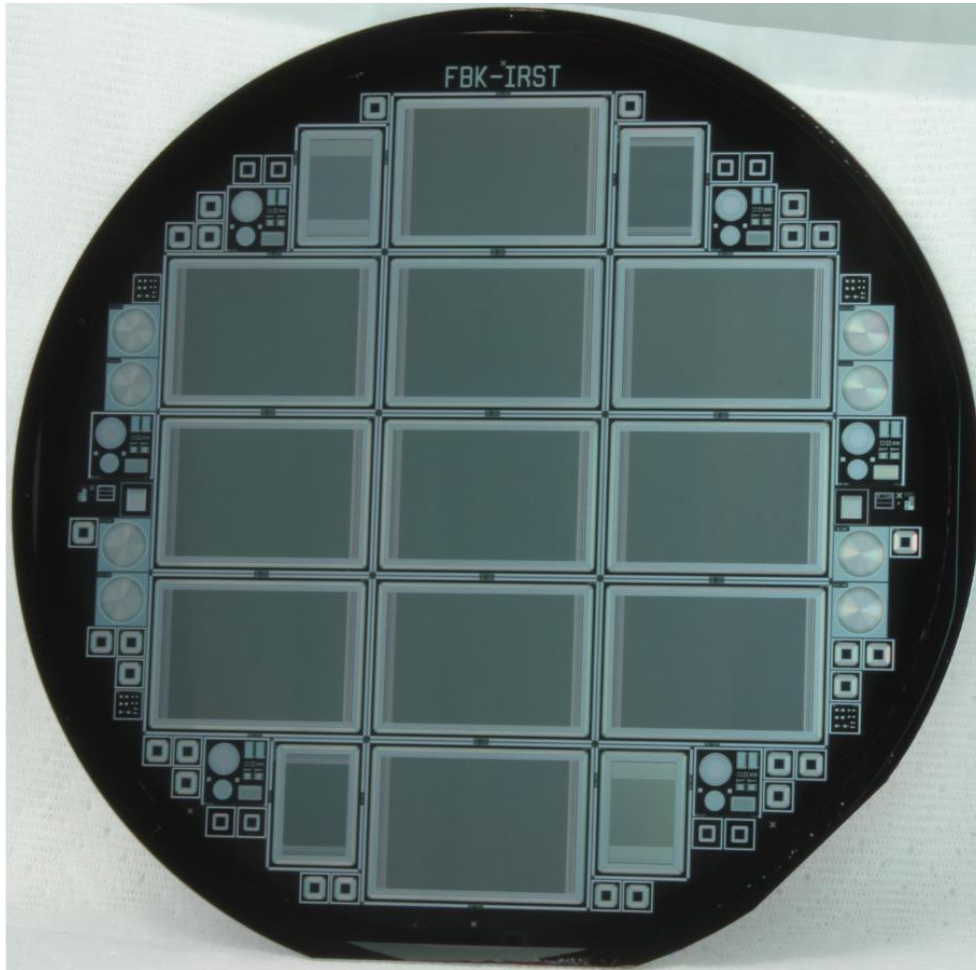
Silicon microstrip detectors:

600 large-area double-sided in spec detectors fabricated in 2003-2005.

Silicon pixel detectors:

p-on-n pixel detectors fabricated in 2006-2007.

Strip Detectors: custom

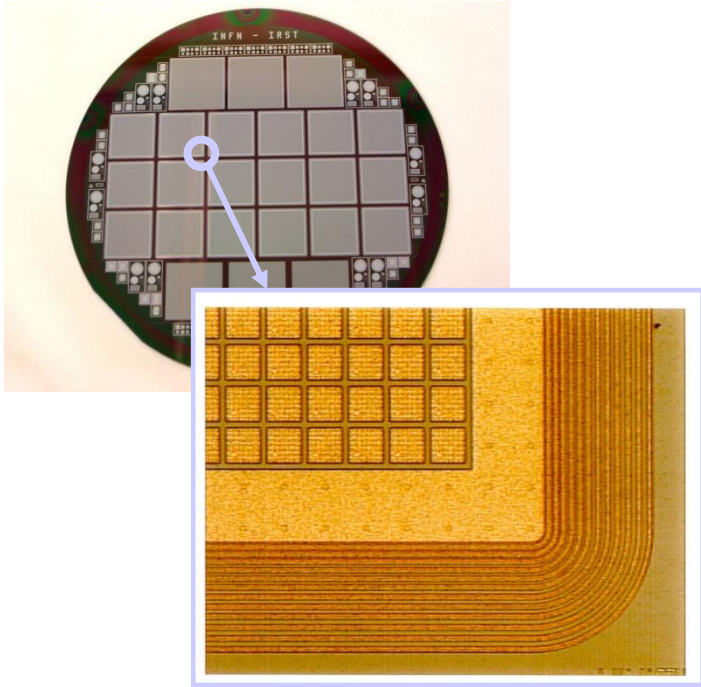


Custom development of strip detectors for private companies:

- single-side,
- DC/AC coupled,
- very low leakage,
- high yield

Pixel detectors: examples

Medipix 1&2

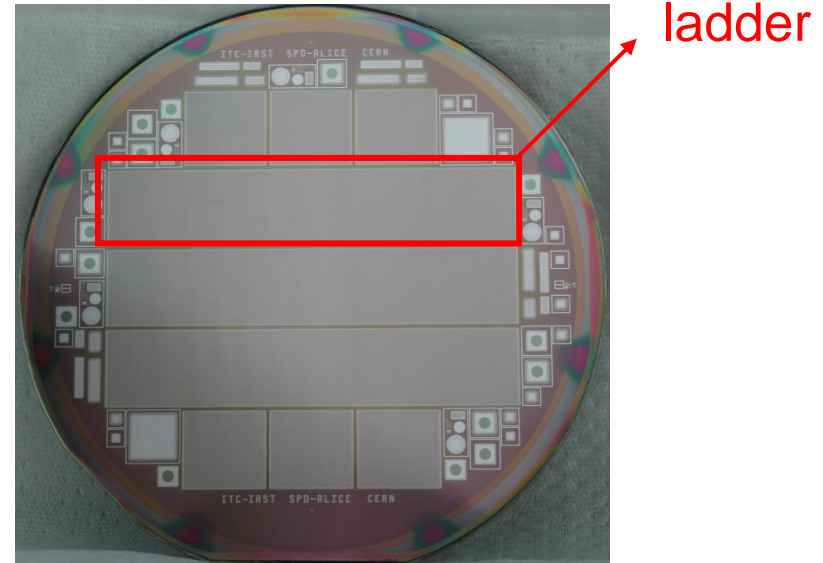


- Medipix1: pixel size $170 \times 170 \mu\text{m}^2$
- Medipix2: pixel size $55 \times 55 \mu\text{m}^2$

Substrate thick.: up to 1.5mm



NA48/ALICE experiment



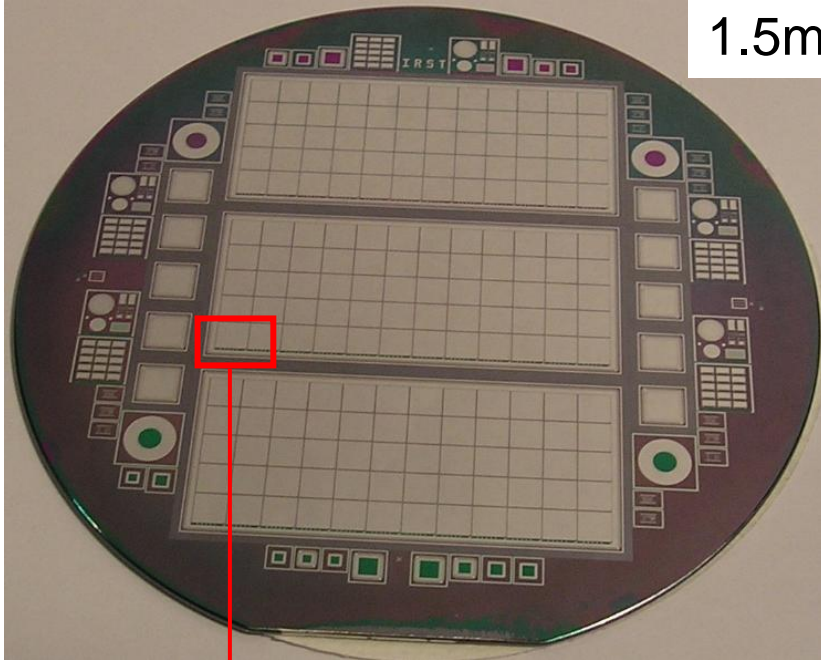
- ALICE SPD layout
- pixel size $50 \times 400 \mu\text{m}^2$

Substrate thickness: 200 μm

Leakage current $\sim 100 \text{pA/cm}^2$ for 300 μm substrates

Thick detectors: example

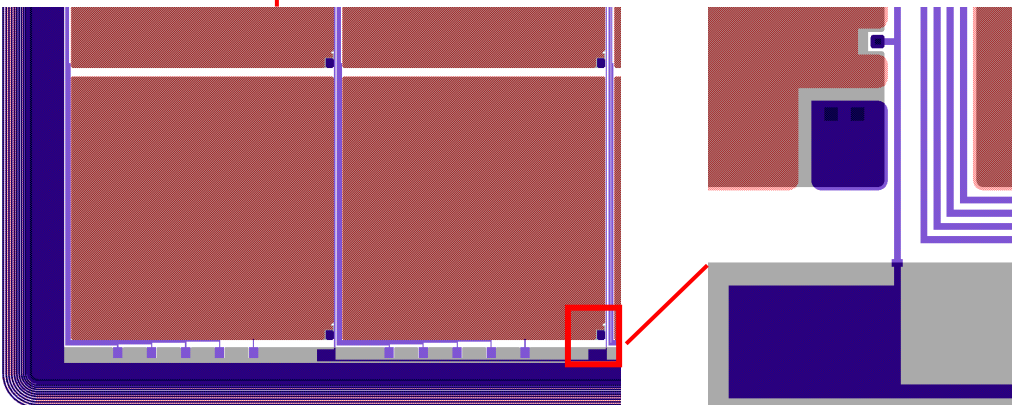
INFN-PD/LNL



1.5mm-thick wafer (also 200 μ m-thick, same design)

PAD detectors for TRACE:

- 12x5 elements
- 4mm pitch (X and Y)
- AC coupling
- punch-through biasing
- termination structure
(voltage handling, lateral depletion)



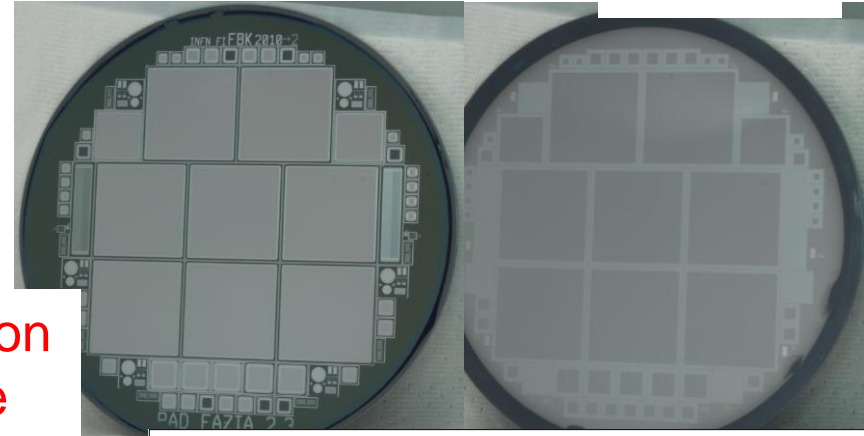
Non standard processing:

- Special quartz supports
- Critical automatic handling
- Starting substrates play a role

Requirements for ΔE -E and pulse-shape analysis

- Non standard substrate orientation: $\sim 8^\circ$ off from $\langle 100 \rangle$
- NTD wafers (high uniformity in resistivity \rightarrow high voltage)
- 2 thicknesses ($300\mu\text{m}$ and $500\mu\text{m}$, $V_{\text{depl}} \sim 120\text{V} \div 300\text{V}$)
- very low dead layers and dead borders
- $2 \times 2\text{cm}^2$ active area
- low sheet resistance
- capable to see visible light

ohmic
side

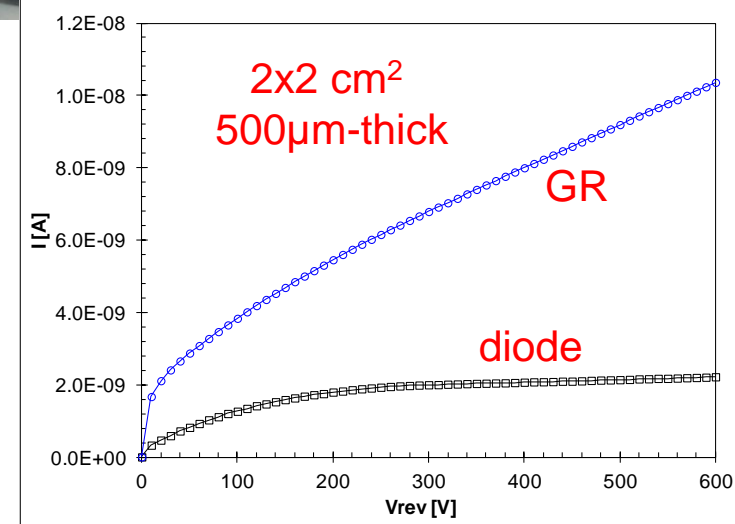


junction
side

Dedicated technology

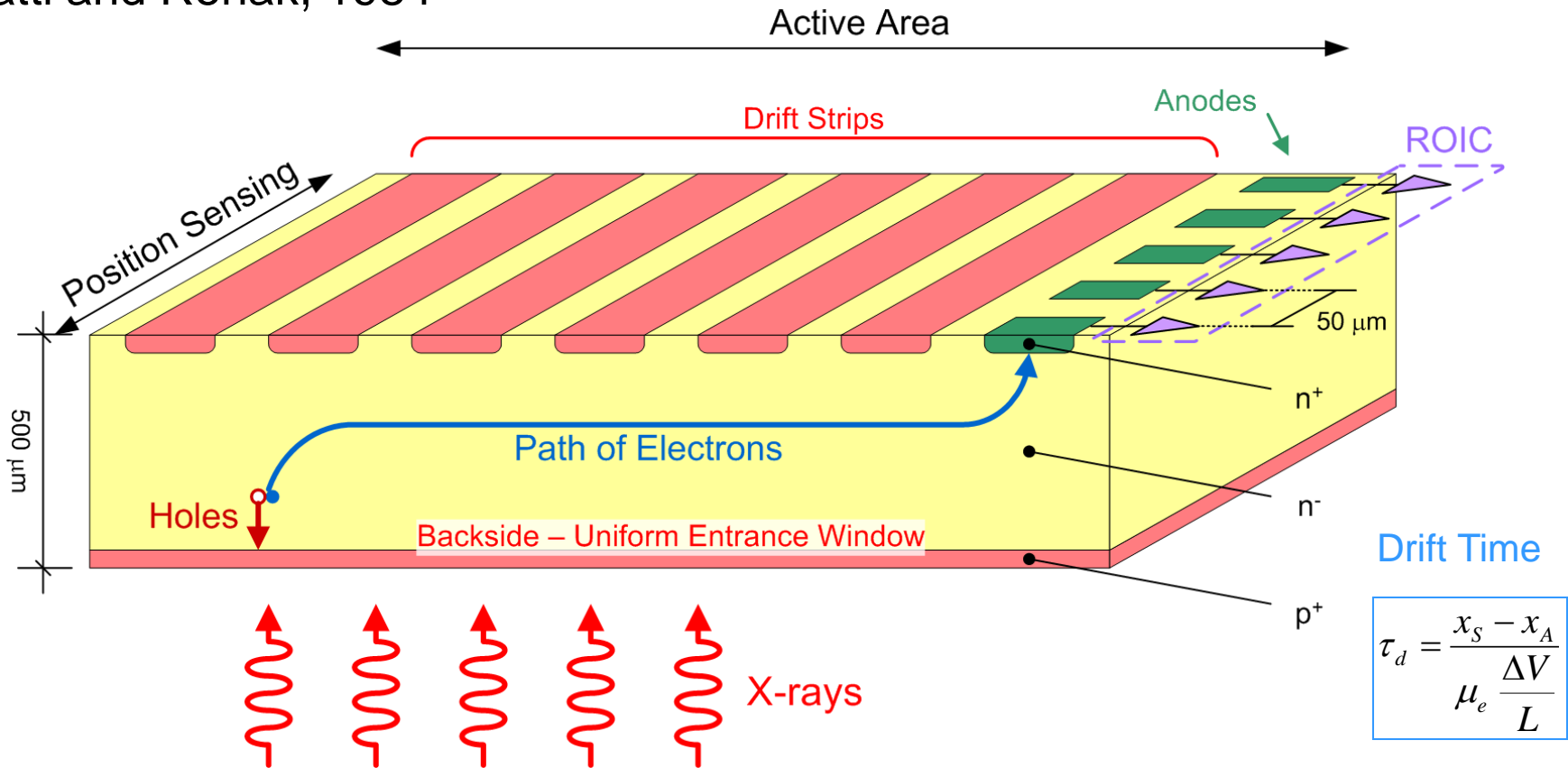
- double side process
- thick + thin ($\sim 30\text{nm}$) metal levels on both sides
- thin junction on front-side; dead layer $\sim 150\text{nm}$
- dead layer at back-side $\sim 700\text{nm}^*$
- dead region at border $\sim 800\mu\text{m}^*$

* different solutions give lower values but kill the yield



Silicon Drift Detectors: R&D

Gatti and Rehak, 1984



Applications:

- spectroscopy
- gamma-ray spectrometry (with scintillator)
- position sensitive detector

3 running projects:

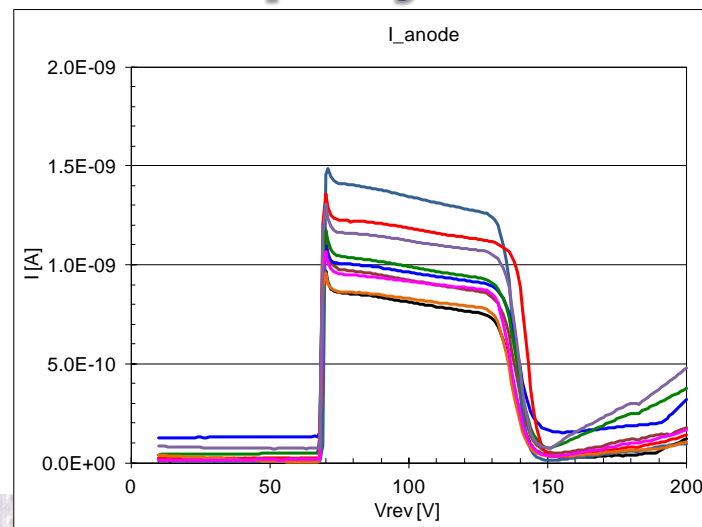
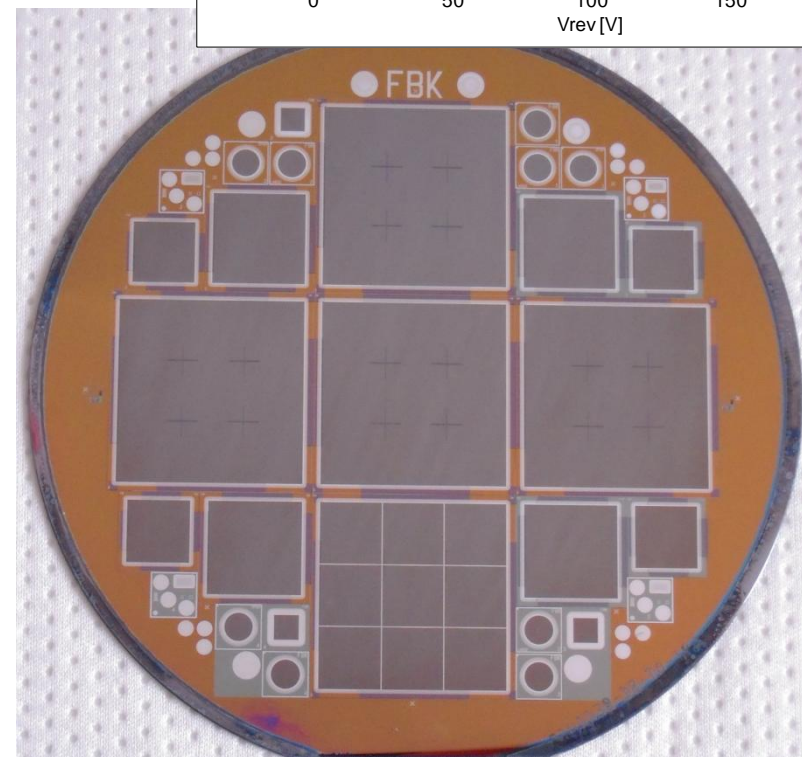
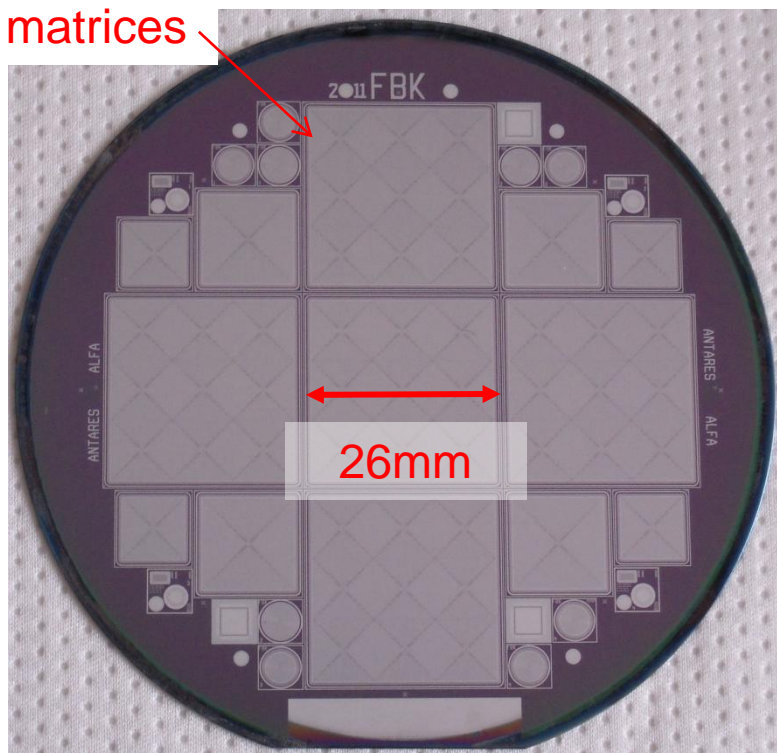
- private contract
- ESA
- INFN

Silicon Drift Detectors: ESA project

ESA/PolIMI/INFN-MI

- double side technology
- γ -ray detector
- $\text{LaBr}_3:\text{Ce}$ scintillator (2" and 3" \varnothing)
- optical entrance window for $\sim 370\text{nm}$ light

3X3 SDD
matrices

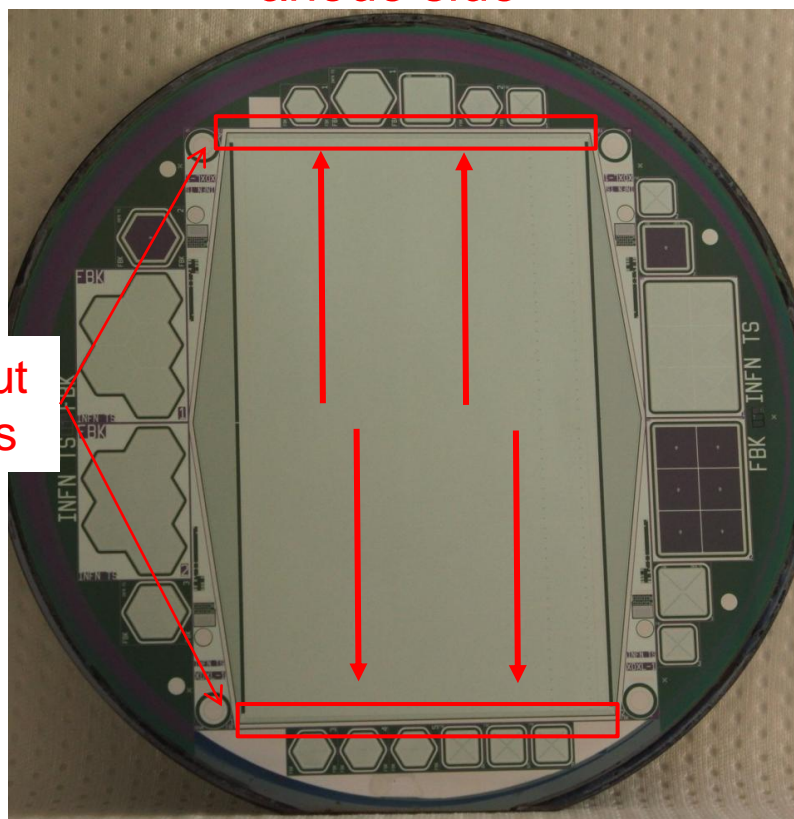


Silicon Drift Detectors: INFN project

INFN-TS

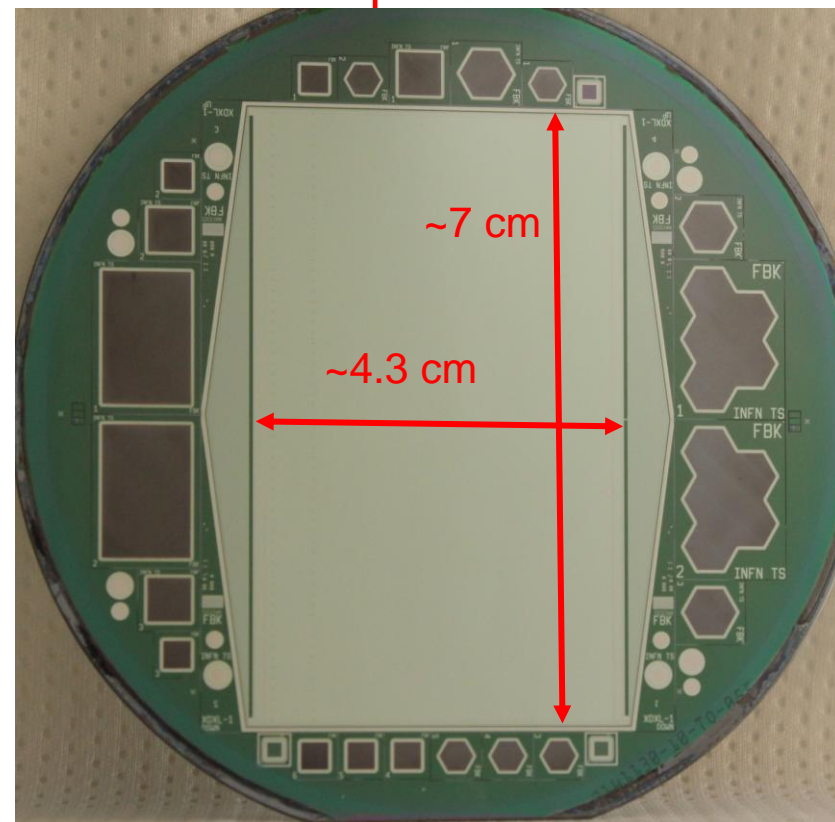
- double side technology
- large area linear SDD device (ALICE-type)
- X-ray detection
- test production capability for LOFT ($\sim 12 \times 7.4 \text{ cm}^2$)

anode side



read-out
anodes

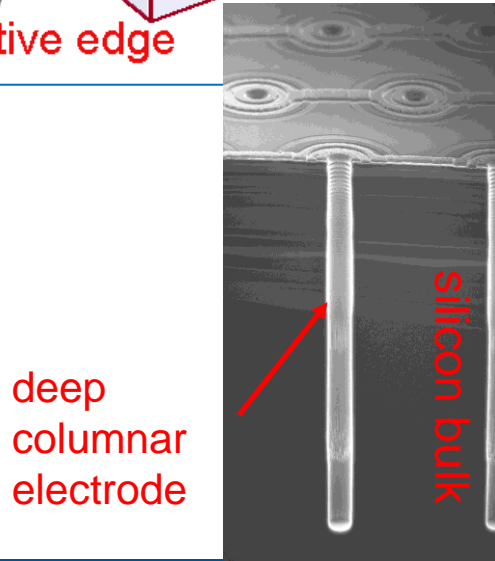
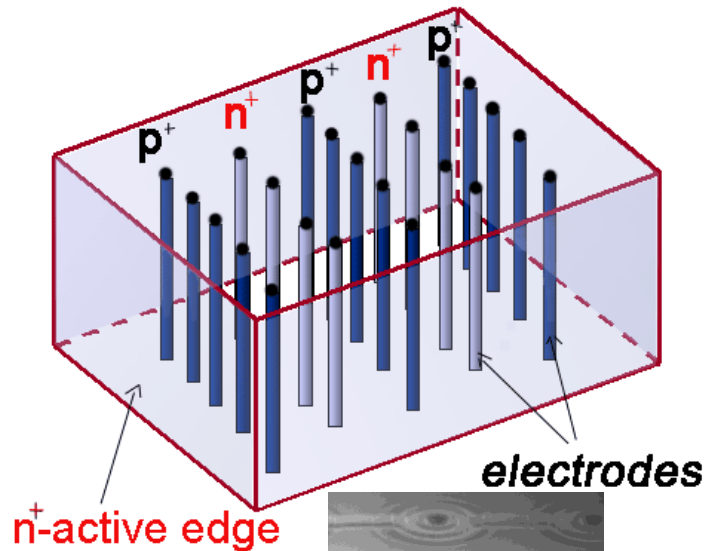
p-side



3D sensors: R&D activity

INFN
CERN

First proposed by S. Parker et. al.
in NIMA 395 (1997), 328



ADVANTAGES:

- Electrode distance and substrate thickness decoupled:
 - low depletion voltage
 - high speed
 - good charge collection efficiency
→ **High radiation hardness**
- Active edges:
- Dead area reduced to few μm from the edge

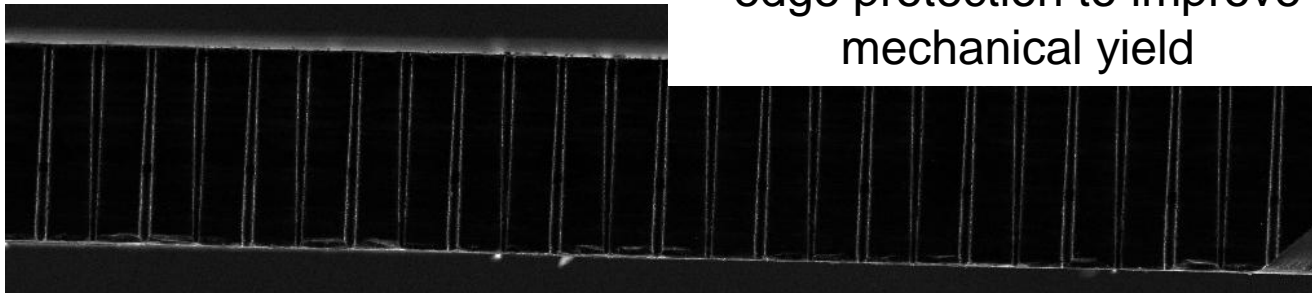
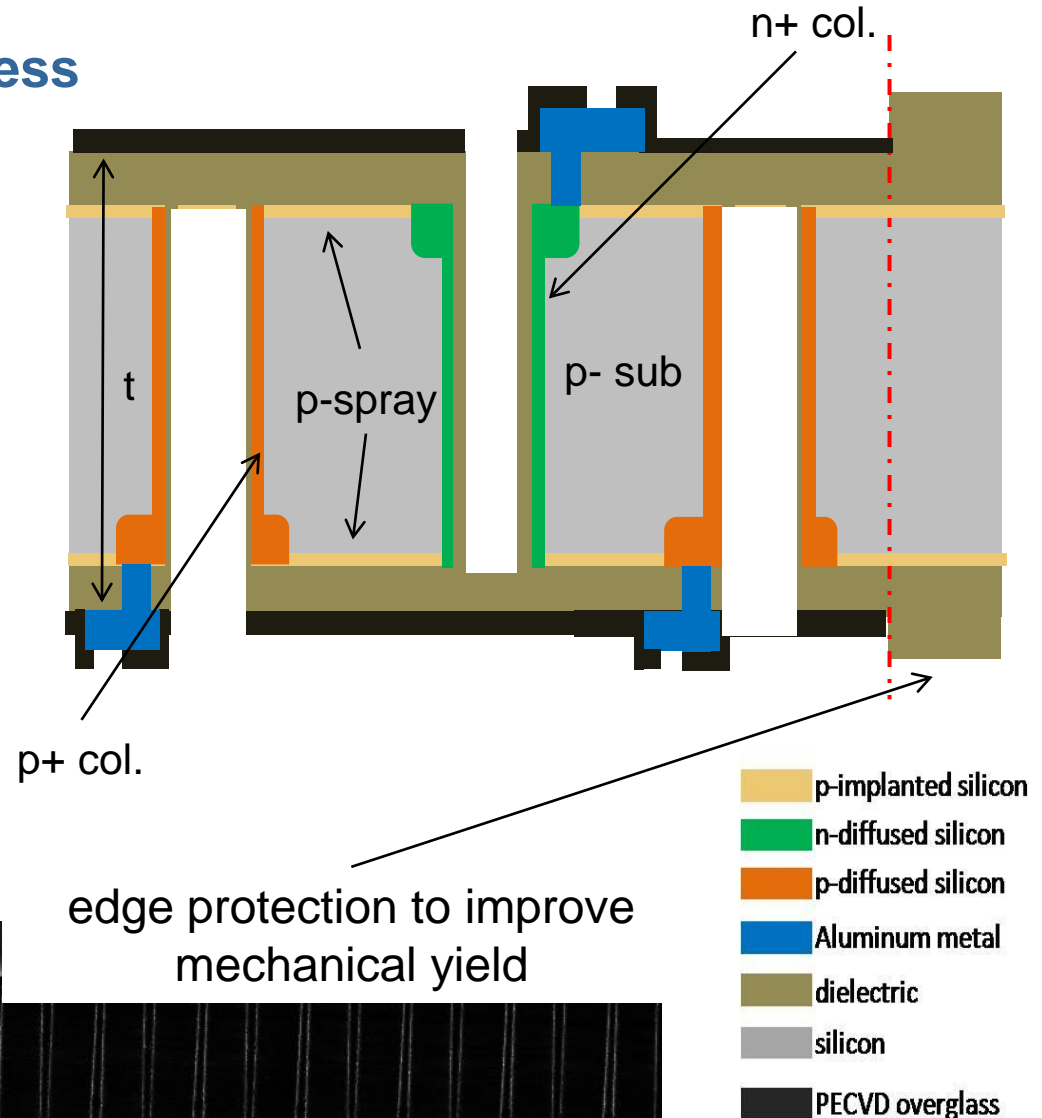
DISADVANTAGES:

- Non uniform response due to electrodes
- **Complicated technology**
- Higher capacitance with respect to planar

FBK 3D technology

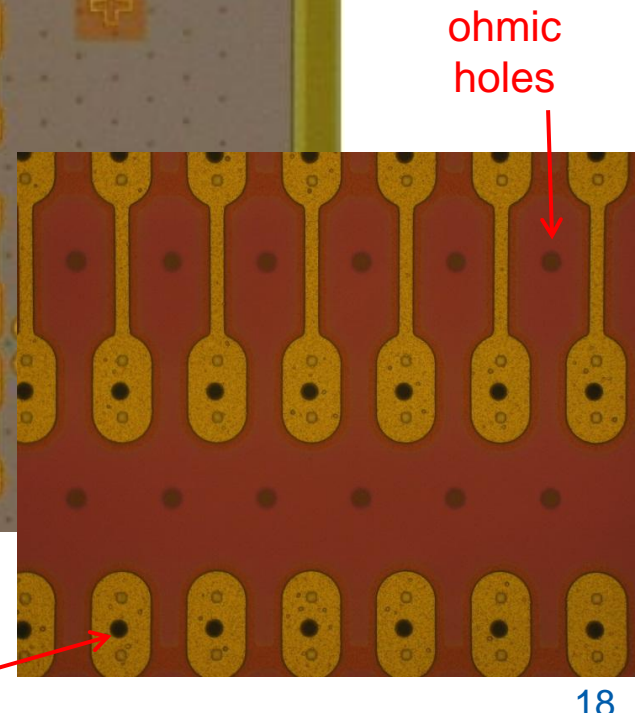
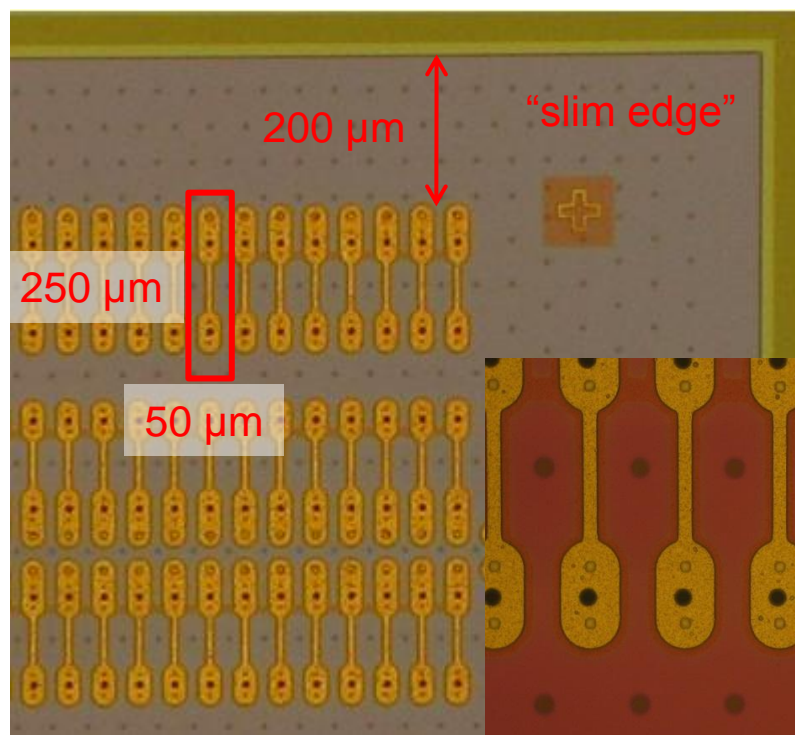
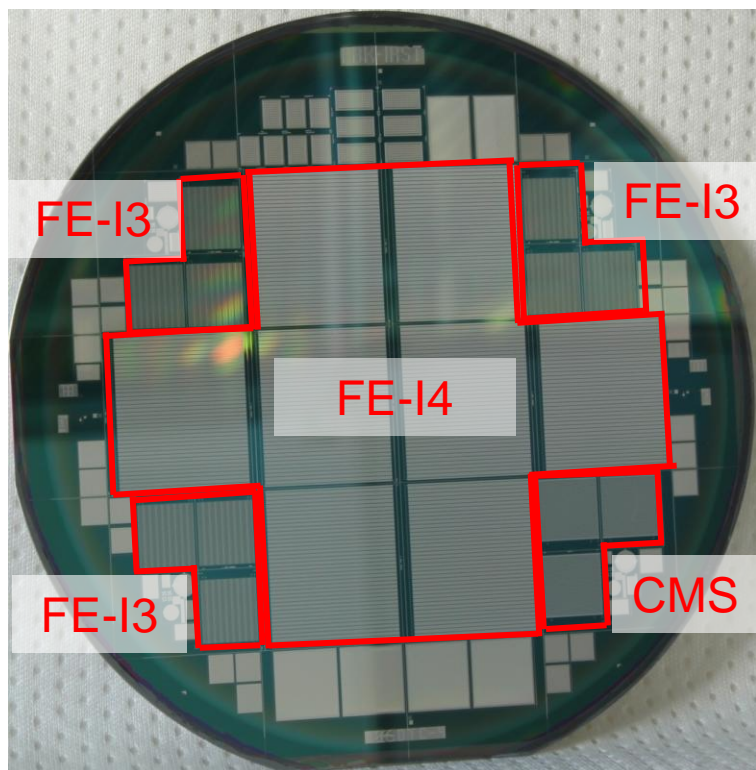
Double side fabrication process

- junction holes etched from front
- ohmic holes etched from back
- empty holes (~11 μ m diam.)
(no poly-Si)
- holes depth equal to the wafer thickness (230 μ m)
- p-type FZ wafer
- p-spray isolation
- edge protection



3D detectors for ATLAS IBL up-grade

- Common layout of *ATLAS 3D sensor Collaboration* (CNM-IMB, SINTEF, SNF, FBK)
- ATLAS FE-I4 compatible 3D pixel detectors
- ~20% of pixel sensors for IBL will be 3D



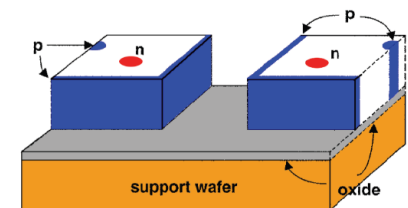
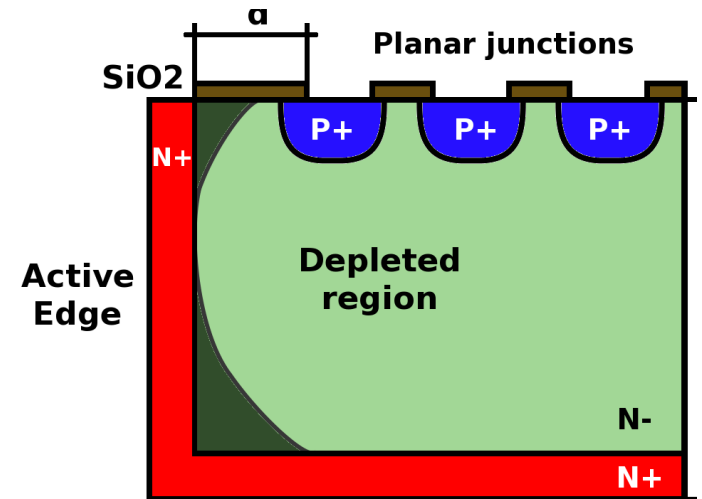
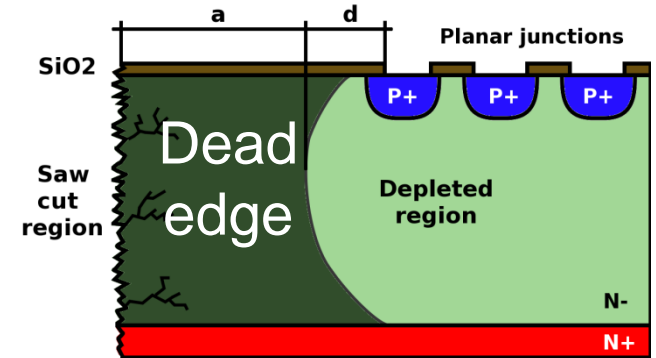
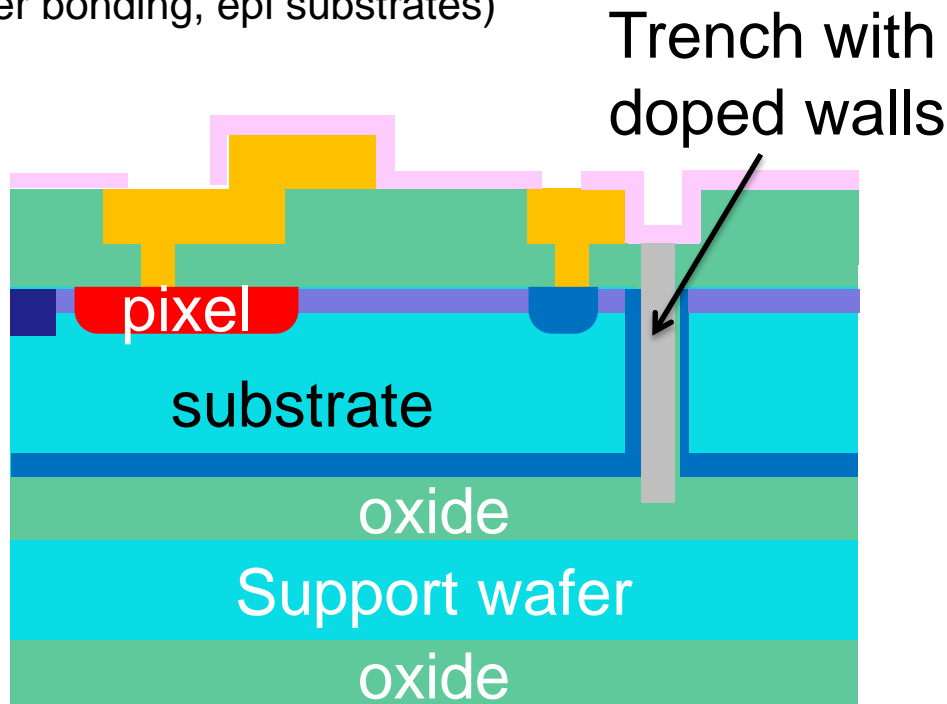
Active edge (edgeless) detectors

Main motivation:

minimize dead area at the borders

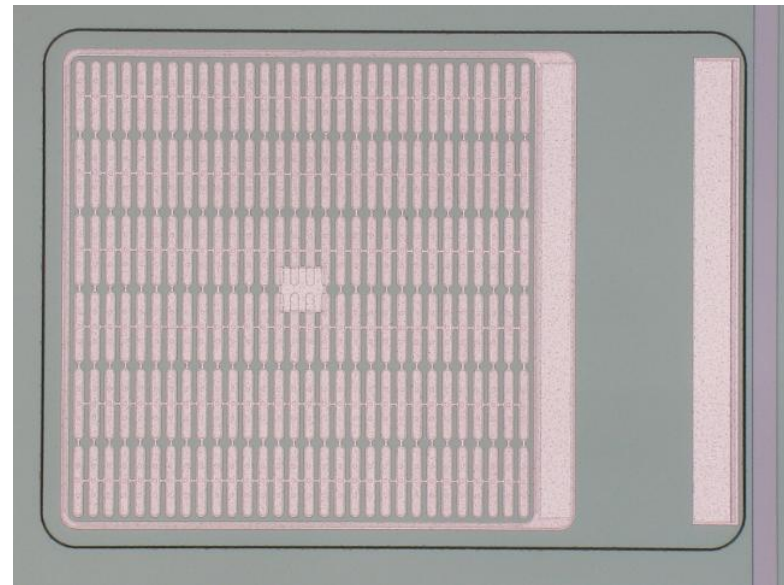
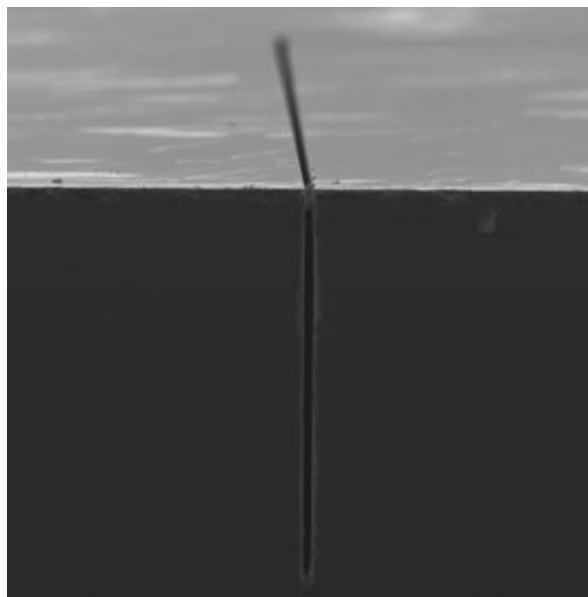
Compatible with both planar and 3D devices

Requires a support wafer
(wafer bonding, epi substrates)

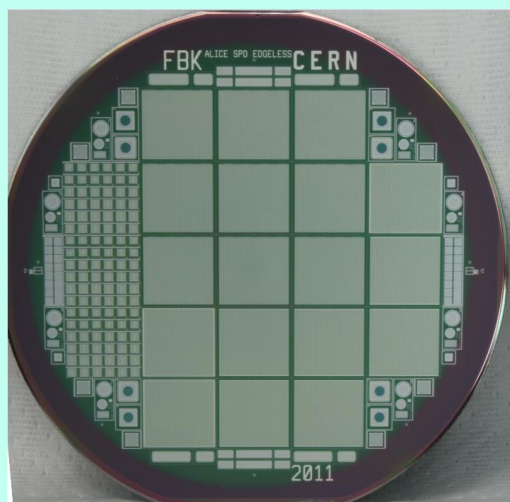


Active edge: example

- 4.5 μm wide trench
- 200 μm deep
- polysilicon filled
- test structures to study collection efficiency at the border



INFN-BA, CERN

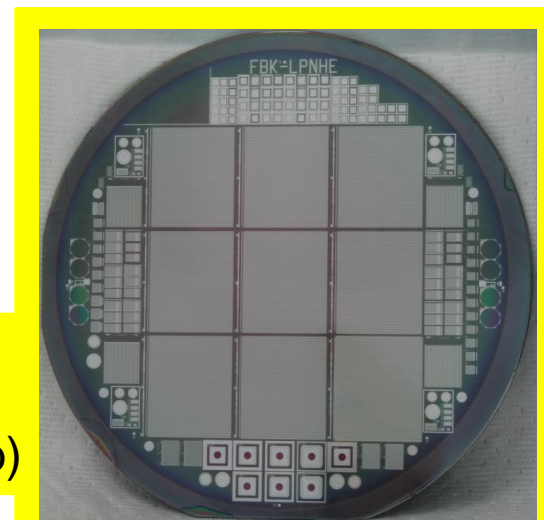


2 running projects:

- pixel sensors compatible with ALICE ROC (epi wafers, 100 μm thick + sub)

- pixel sensors compatible with ATLAS FE-I4 (200 μm -thick FZ + waf-bond sub)

LPNHE Paris



Low-level light sensors

Avalanche Geiger-mode photodiodes

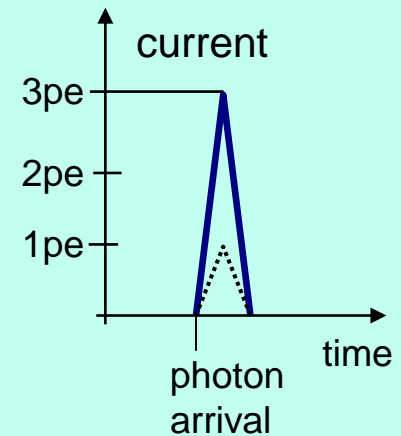
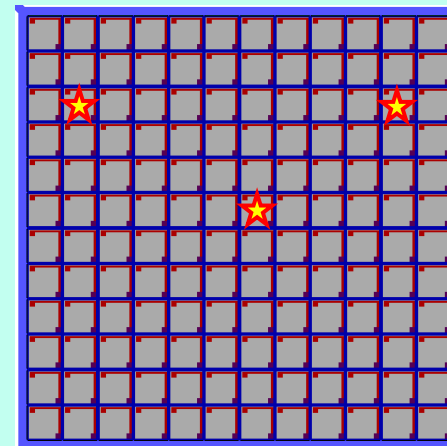


Each photon triggers a discharge which is shortly quenched

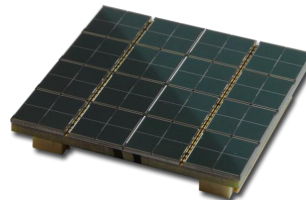
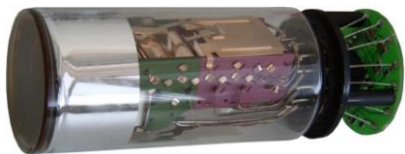


- Gain $\sim 10^6$
- Timing $\sim 100\text{ps} / 1\text{ph.e.}$
- Bias voltage $< 100\text{V}$
- Sensitivity $\sim 1\text{ ph. e.}$
- QE \sim medium

Array of tiny GM APDs: proportionality



SiPM:
Silicon Photo-Multiplier



From vacuum...

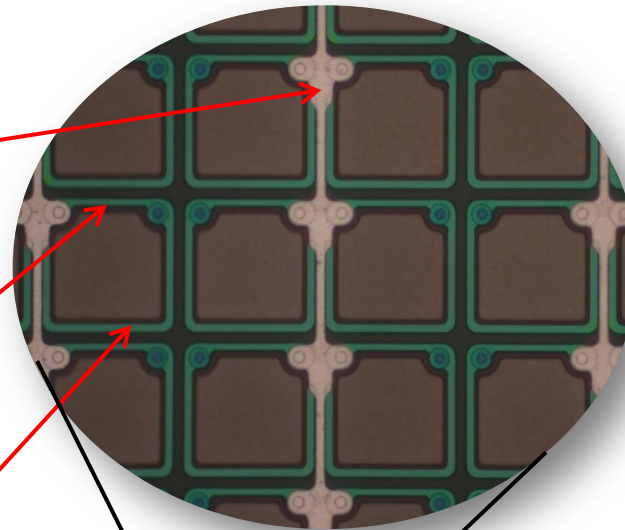
...to solid-state

Device Layout: example

Metal line connecting
all cells in parallel
(one common anode)

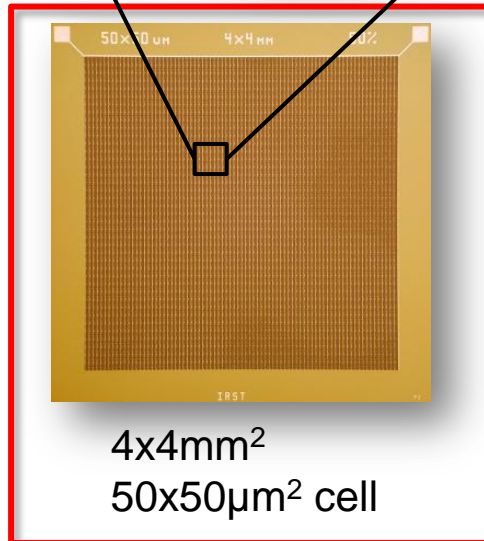
Polysilicon
resistor

Field-plate
to reduce electric
field around the
junction



The cathode is
contacted on the
back side

Resistor is located
outside the active
Area → no fill factor
loss



Fill Factor

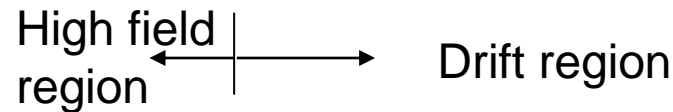
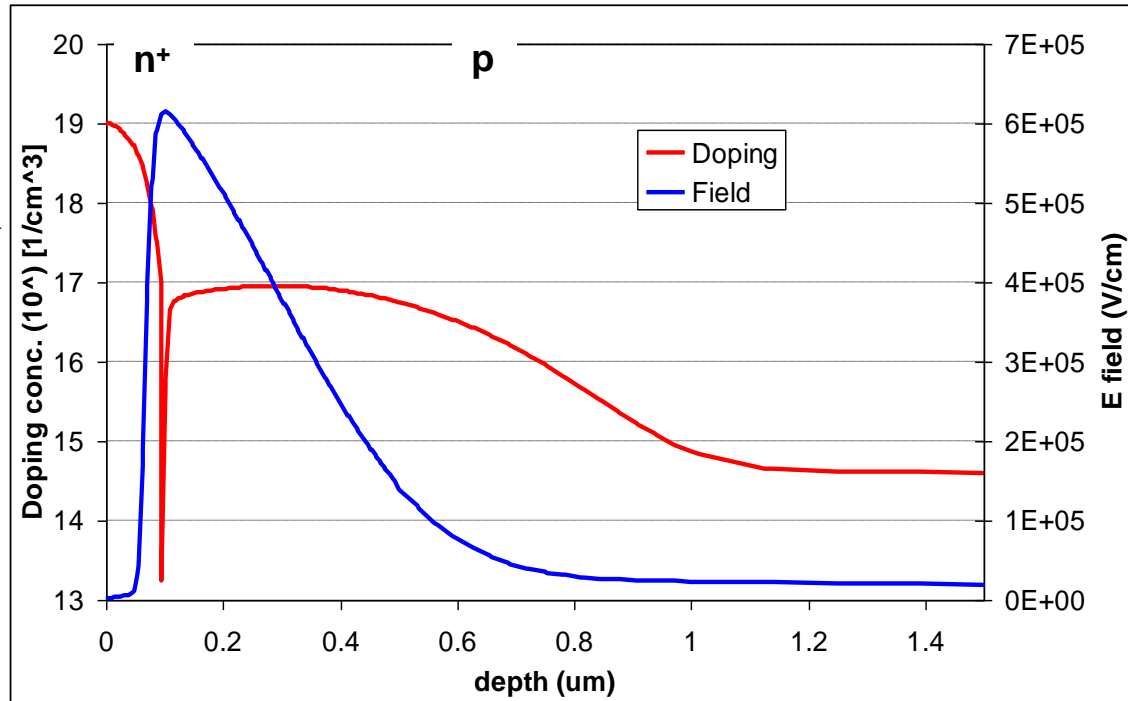
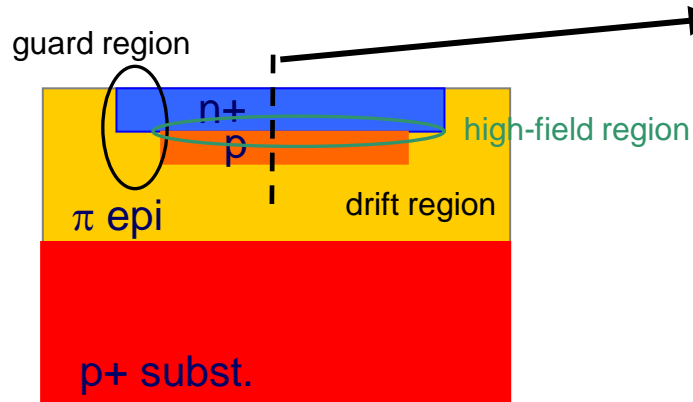
~ 45% 40x40 µm² cell

~ 55% 50x50 µm² cell

~ 72% 100x100 µm² cell

FBK original technology

Shallow-junction SiPM N-on-P technology



- 1) Substrate: p-type epitaxial
- 2) Very thin n⁺ layer
- 3) Quenching resistance made of doped polysilicon
- 4) Anti-reflective coating optimized for $\lambda \sim 420\text{nm}$

FBK SiPM R&D

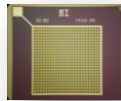
2005

**MEMS
agreement
PAT/FBK/INFN**

One of the main topics was develop. and application of SiPMs

2006

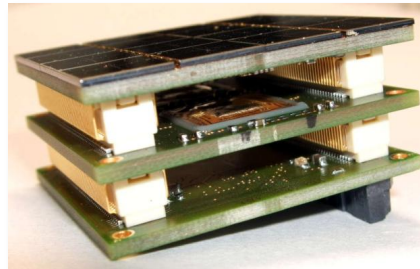
1x1mm²
40x40μm² cell



2008

**FP7 project
HYPERimage**

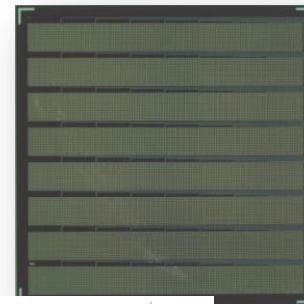
With Philips.
Develop. of a
PET/MR system



2009

**MEMS2
agreement
FBK/INFN**

SiPM is again
one of main
topics



2010

**FP7 project
SUBLIMA**

Improvements:

- Junction techn.
- Small cell size
- Interconnections

2012

2014

!!Spin-off company on this subject:

AdvanSiD
Advanced Silicon Detectors

<http://www.advansid.com/>

...what applications?

Nuclear medicine:

PET

intra-operative probes



Biology:

Confocal Fluorescence
Microscopy

Real Time PCR

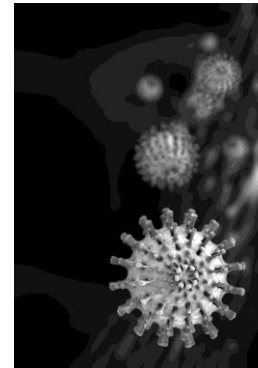
Flow Citometry

Physics experiments:

Cosmic rays detections

Gamma

X-rays detections



Materials analysis:

SEM

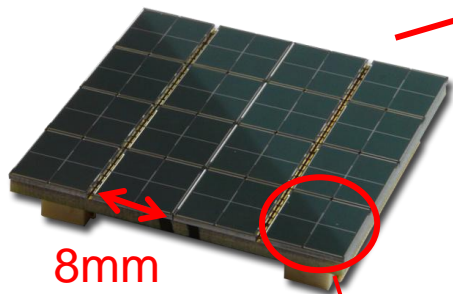
Homeland
security



HyperImage preclinical system

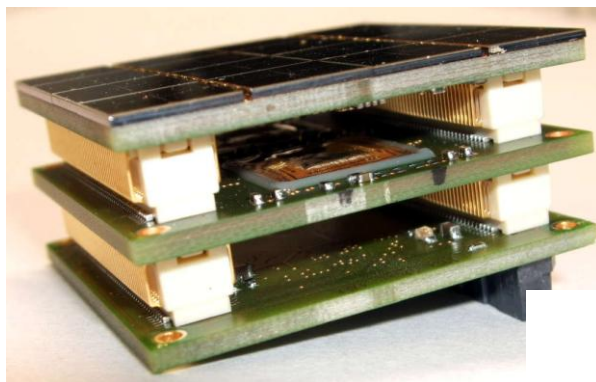
The stack

SiPM tile

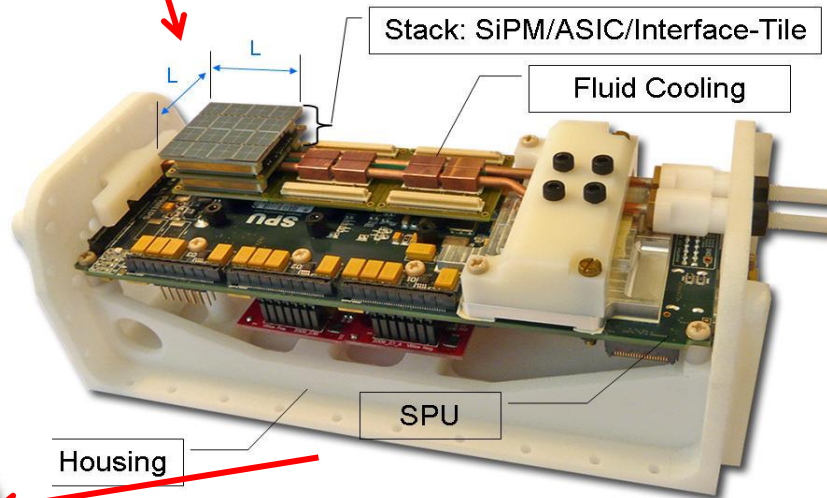


8mm

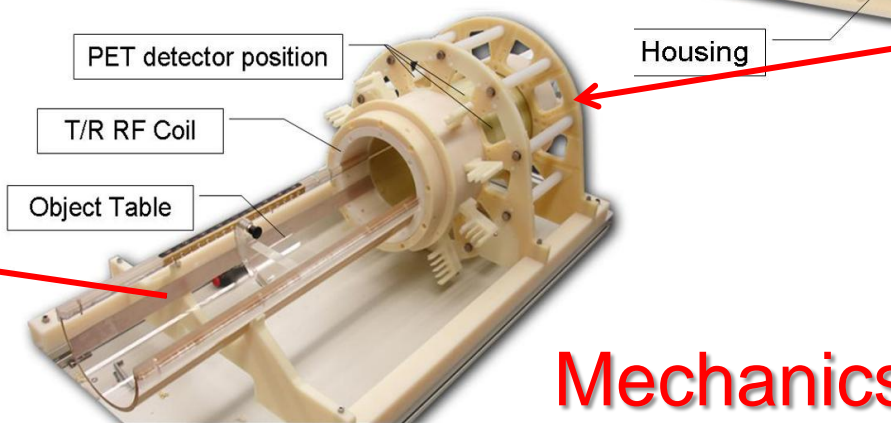
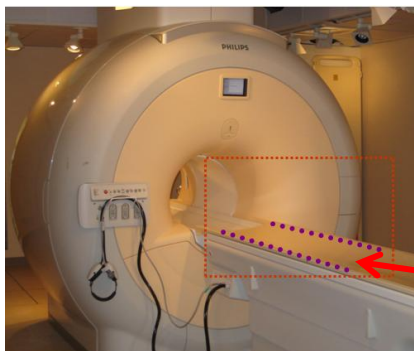
FBK monolithic QUAD



The module



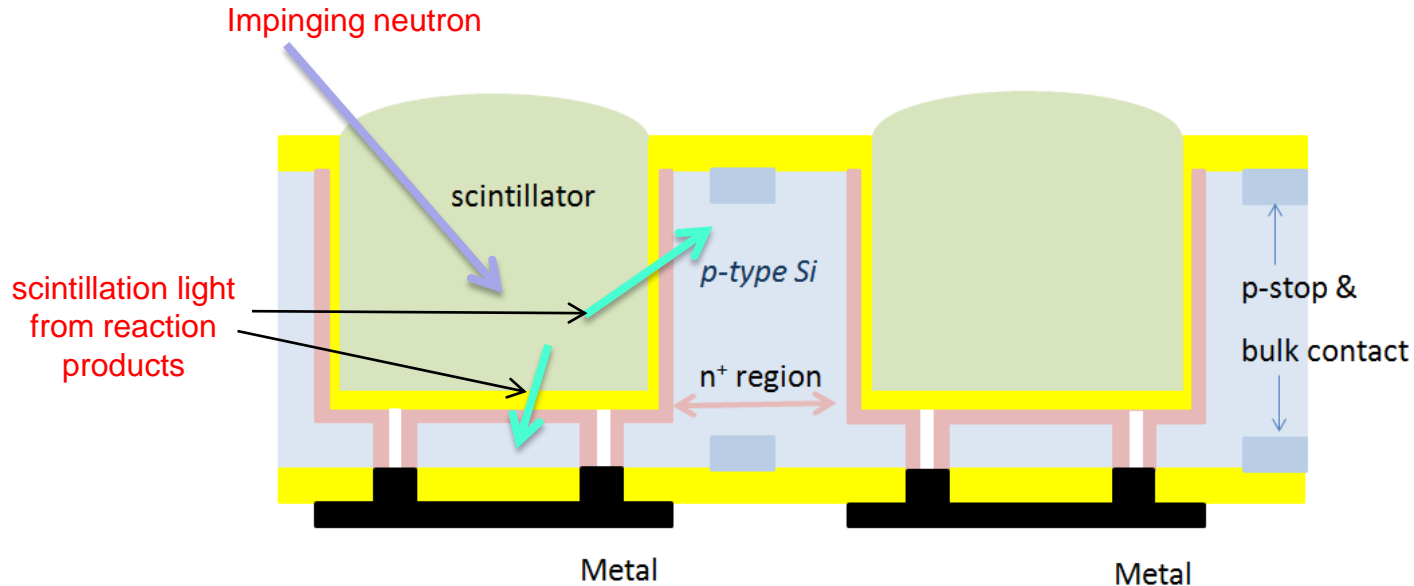
PET-MR



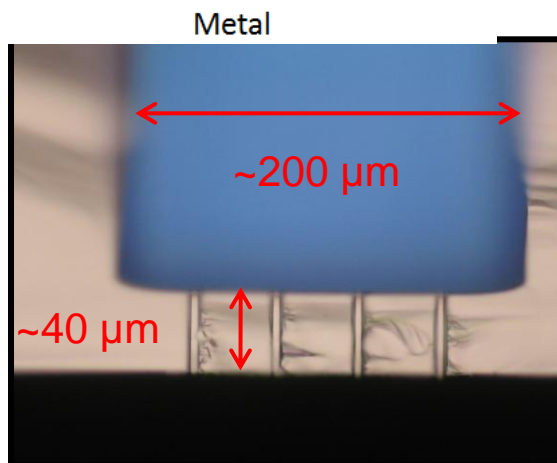
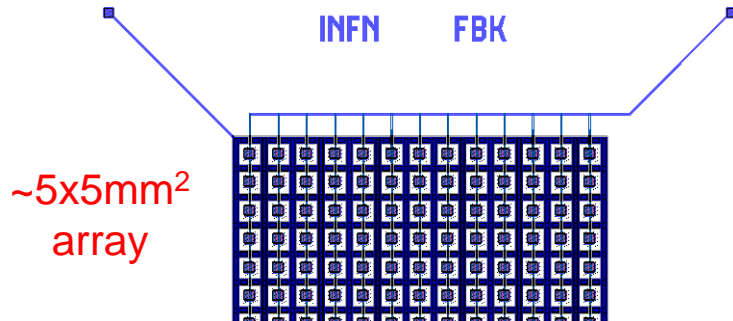
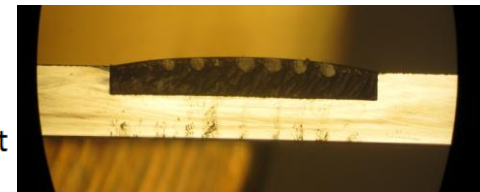
Mechanics

Neutron detector for HYDE

- R&D project with INFN TN-PD
- idea: increase interaction volume and light collection surface
- use of polysiloxane based scintillator



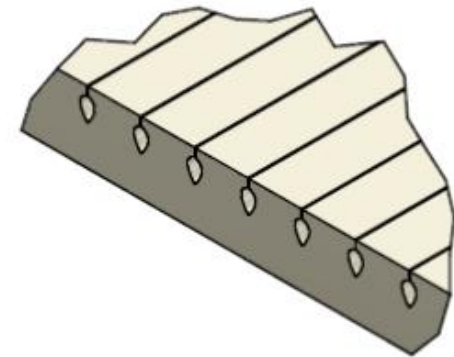
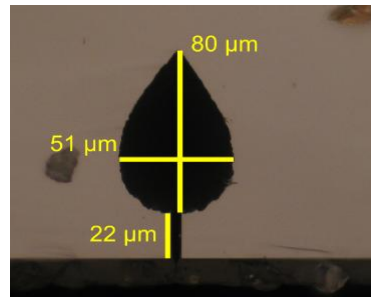
preliminary
filling tests



Silicon buried channels

... not only detectors

- R&D project with INFN PI
- integrate in the same silicon substrate the cooling system
- based on microchannels obtained by DRIE
- channel section determined by DRIE process
- channel length defined by the layout



Other activities

- Rad-hard studies on different Si sub types (FZ, Cz, epi, p-type, ...)
- JFET based active elements integrated on the detector substrate
- BJT-based detectors for radon detection
- Diode array for dosimetry applications
- Supports for CNT: surface preparation and electrode definition